

In response to the outstanding Official Action, kindly amend the subject application as follows:

IN THE CLAIMS:

Kindly cancel claims 1-11, 28-34, 36, 37 and 39-44 without prejudice or disclaimer.

Please amend claims 15, 35, 45 and 55 as follows. A marked-up version showing the changes made thereto is enclosed.

A1 --15. (Amended) A processing apparatus having a processing space for processing a substrate or a film therein and an exhaust means for exhausting a gas from the processing space, comprising means provided between the processing space and the exhaust means, for causing a chemical reaction in a non-reacted gas and/or a by-product during processing of the substrate or the film, wherein the means comprises a heat generating member comprising phosphorous (P) atoms, wherein the amount of phosphorous atoms contained in the heat generating member is 0.1% or more in an atomic composition ratio relative to total atomic components constituting the heat generating member.

A2 35. (Amended) A processing apparatus having a processing chamber and an exhaust means for exhausting a gas from the processing chamber, comprising, in an exhaust path connecting the processing chamber and the exhaust means, a region with a different mean velocity of the gas from that of the processing chamber, and a chemical reaction causing means provided in the region, for causing a chemical reaction in a non-

A2
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reacted gas and/or a by-product exhausted from the processing chamber, wherein the mean velocity of the gas of the region having the chemical reaction causing means is larger than the mean velocity of the processing chamber, and wherein the chemical reaction causing means comprises a high-melting metal filament.

A3
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45. (Amended) A processing apparatus having a processing space and an exhaust means for exhausting a gas from the processing space, comprising a chemical reaction causing means provided in an exhaust path connecting the processing space and the exhaust means, for causing a chemical reaction in a non-reacted gas and/or a by-product during the processing, and a cooling means disposed in the exhaust path in the vicinity of the chemical reaction causing means and provided on the side of the exhaust means of the chemical reaction causing means.

A4
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55. (Amended) A processing apparatus having a processing space and an exhaust means for exhausting a gas from the processing space, comprising a chemical reaction causing means provided in an exhaust path between the processing space in a chamber and the exhaust means, for causing a chemical reaction in a non-reacted gas and/or a by-product during the processing, and a cooling means provided in at least a part of the exhaust path between the processing space and the exhaust means.--
